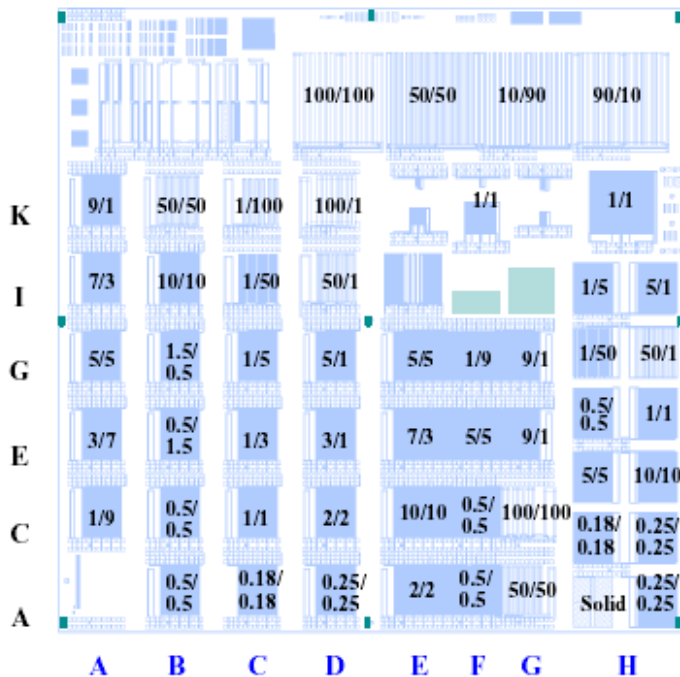


SKW Associates, Inc,

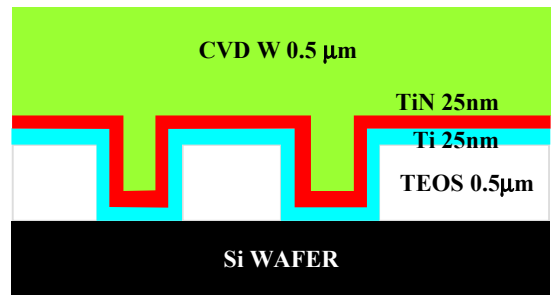
3370 Victor Court
 Santa Clara, CA 95054
 Phone (408) 919-0094
 Fax (408) 919-0097
 Email: skw@testwafer.com
<http://www.testwafer.com>

SKW 5-3 300mm Wafer Specifications

DATE: November 18, 2004



SKW5-3 Mask Floor Plan



Cross Sectional View

PE-TEOS Oxide Film Thickness

PARAMETER	NOMINAL	TOLERANCE
Lot-to-Lot	3000 Å	+/- 5%
Within-Lot (Wafer-to-Wafer)		+/- 5%
Within-Wafer		+/- 3%
Within-Die		+/- 3%

PVD Ti Film Thickness

PARAMETER	NOMINAL	TOLERANCE
Lot-to-Lot	250 Å	+/- 5%
Within-Lot (Wafer-to-Wafer)		+/- 5%
Within-Wafer		+/- 5%
Within-Die		+/- 5%

PVD TiN Film Thickness

PARAMETER	NOMINAL	TOLERANCE
Lot-to-Lot	250 Å	+/- 5%
Within-Lot (Wafer-to-Wafer)		+/- 5%
Within-Wafer		+/- 5%
Within-Die		+/- 5%

CVD W Film Thickness

PARAMETER	NOMINAL	TOLERANCE
Lot-to-Lot	5000 Å	+/- 10%
Within-Lot (Wafer-to-Wafer)		+/- 10%
Within-Wafer		+/- 5%
Within-Die		+/- 5%

Specification for Patterning

PARAMETER	NOMINAL	TOLERANCE
Center Die X Location	-10.000 mm	+/- 100 μm
Center Die Y Location	-10.000 mm	+/- 100 μm
Die Size: X	20 mm	+/- 10 μm
Die Size: Y	20 mm	+/- 10 μm
Die Spacing X/Y	180 / 360 μm	+/- 10 μm
	360 μm	+/- 10 μm

Line Width Variation (measured on 2 μm structures)

PARAMETER	NOMINAL	TOLERANCE
Lot-to-Lot	2 μm	+/- 0.1 μm
Within-Lot (Wafer-to-Wafer)		+/- 0.1 μm
Within-Wafer		+/- 0.1 μm
Within-Die		+/- 0.1 μm